Radiation Report TLV4H290-SEP Single-Event Effects (SEE) Radiation Report

TEXAS INSTRUMENTS

The purpose of this study was to characterize the effects of heavy-ion irradiation on the single-event latch-up (SEL) performance of the TLV4H290-SEP high precision quad comparator. Heavy-ions with an LET_{EFF} of 50.5MeV-cm²/mg were used to irradiate the device with a fluence of 1 × 10^7 ions/cm². The results demonstrate that the TLV4H290-SEP is SEL-immune up to LET_{EFF} = 43MeV-cm²/mg at 125° C.

Characterization of single-event transients (SET) was also performed, up to a surface LET_{EFF} = 50.5MeV-cm² / mg at 125° C.

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1 Overview

The TLV4H290-SEP is quad channel comparator which offers low input offset voltage, fault-tolerant inputs with an excellent speed-to-power combination with a propagation delay of 100ns. The TLV4H290-SEP comparator has an open-drain output stage that can be pulled below or beyond the positive supply voltage, making TLV4H290-SEP appropriate for level translation.

DESCRIPTION	DEVICE INFORMATION				
TI Part Number	TLV4H290-SEP				
MLS Number	TLV4H290MDYYTSEP				
Device Function	Radiation-Tolerant High-Precision Quad Comparator in Space Enhanced Plastic				
Technology	LBC9 BiCMOS				
Exposure Facility	Facility for Rare Isotope Beams, Michigan State University				
Heavy Ion Fluence per Run	1×10 ⁷ ions/cm ²				
Irradiation Temperature	125°C (for SEL testing)				

Table 1-1. Overview Information

2 SEE Mechanisms

The primary single-event effect (SEE) events of interest in the TLV4Hx90-SEP are single-event latch-up (SEL). From a risk/impact point-of-view, the occurrence of an SEL is potentially the most destructive SEE event and the biggest concern for space applications. The LBC9 BiCMOS process was used for the TLV4H290-SEP. CMOS circuitry introduces a potential for SEL susceptibility. SEL can occur if excess current injection caused by the passage of an energetic ion is high enough to trigger the formation of a parasitic cross-coupled PNP and NPN bipolar structure (formed between the p-sub and n-well and n+ and p+ contacts). The parasitic bipolar structure initiated by a single-event creates a high-conductance path (inducing a steady-state current that is typically orders-of-magnitude higher than the normal operating current) between power and ground that persists (is "latched") until power is removed or until the device is destroyed by the high-current state. The process modifications applied for SEL-mitigation were sufficient as the TLV4H290-SEP exhibited no SEL with heavy-ions up to an LET_{EFF} of 50.5MeV-cm²/mg at a fluence of 10⁷ ions/cm² and a chip temperature of 125°C.

This study was performed to evaluate the SEL effects with a bias voltage of 5.5V on V+ Supply Voltage. Heavy ions with $LET_{EFF} = 50.5MeV-cm^2/mg$ were used to irradiate the devices. Flux of 10^5 ions/s-cm² and fluence of 10^7 ions/cm² were used during the exposure at $125^{\circ}C$ temperature.



3 Test Device and Test Board Information

The TLV4H290-SEP are packaged in a 14-pin, SOT-23 shown with pinout in Figure 3-1.



Figure 3-1. TLV4H290-SEP Pinout Diagram

Qualification Devices and Test Board

The TLV4H290-SEP was biased in either an output high or output low condition in single supply, where V+ was set to +5.5V and V- was set to GND (0V). The outputs are tied to +5.5V through $20k\Omega$ pull-up resistors.

To achieve an output high state, IN+ was biased with +1V and IN- was biased with +0.5V. For an output low condition, IN+ was biased with +0.5V and IN- was biased with +1V.

Heavy ions with LET_{EFF} =50.5MeV-cm² / mg were used to irradiate the devices. A nominal flux of 10^5 ions / s-cm² and fluence of 10^7 ions / cm² were used during the exposure at 125° C.



Figure 3-2. TLV4H290-SEP Bias Diagram - Output Low



Figure 3-3. TLV4H290-SEP Bias Diagram - Output High





Figure 3-4. TLV4H290-SEP Bias Board for SEL Testing

4 Irradiation Facility and Setup

The heavy ion species used for the SEE studies on this product were provided and delivered by the Michigan State University (MSU) Facility for Rare Isotope Beams using a linear particle accelerator ion source. Ion beams were delivered with high uniformity over a 17mm × 18mm area for the in-air station. A current-based measurement is performed on the collimating slits, which intercept 90-95% of the total beam, and this measurement is cross-calibrated against Faraday cup readings. These measurements are real-time continuous and establish dosimetry and integrated fluence. In-vacuum and in-air scintillating viewers are used for measurement of the beam size and distribution. An ion flux of 10^5 ions / s-cm² was used to provide heavy ion fluences to 10^7 ions / cm².

5 Results

5.1 Single Event Latchup (SEL) Results

During SEL characterization, the device was heated using forced hot air, maintaining the IC temperature at 125°C. The temperature was monitored by means of a thermal camera. The species used for the SEL testing was a Xenon (129 Xe) ion with an angle-of-incidence of 0° for an LET_{EFF} = 50.5 MeV-cm² /mg. A flux of approximately 10⁵ ions/cm² -s and a fluence of approximately 10⁷ ions were used each run. The V+ supply voltage is supplied externally on board at recommended maximum voltage setting of 5.5V. Run duration to achieve this fluence was approximately less than 2 minutes. Two devices were tested (one at output low and the other at output high condition) where each device had a total of two runs. Supply current also includes output pullup-current.

RUN #	DUT	Output Condition	DISTANCE (mm)	TEMPERATURE (°C)	ION	ANGLE	FLUX (ions∙cm²/ mg)	FLUENCE (# ions)	LET _{EFF} (MeV.cm²/m g)
50	2	Low	40	125	¹²⁹ Xe	0	1.02E+05	1.00 E+07	50.5
51	2	Low	40	125	¹²⁹ Xe	0	1.02E+05	1.00 E+07	50.5
52	3	High	40	125	¹²⁹ Xe	0	1.01E+05	1.00 E+07	50.5
53	3	High	40	125	¹²⁹ Xe	0	1.00E+05	1.00 E+07	50.5

Table 5-1. TLV4H290-SEP SEL Conditions Using Xe at an Angle-of-Incidence of 0°

No SEL events were observed, indicating that the TLV4H290-SEP is SEL-immune at LET_{EFF} = 43MeV-cm²/mg and T = 125° C. Using the MFTF method described and combining (or summing) the fluences of the two runs at 125° C (2 × 10^{7}), the upper-bound cross-section (using a 95% confidence level) is calculated as:

 σ SEL $\leq 1.84 \times 10^{-7}$ cm² for LET_{EFF} = 43MeV-cm²/mg and T = 125°C.



Figure 5-1. Run #50: DUT2 Supply Current Versus Time









Figure 5-3. Run #52: DUT3 Supply Current Versus Time



Figure 5-4. Run #53: DUT3 Supply Current Versus Time

5.2 Single Event Transient (SET) Results

The TLV4H390-SEP was characterized from 50.5 to 1.0 MeV-cm²/mg at 1.65V and 3.3V supply voltages in both output high and output low configuration. The device was tested at room temperature for all SETs runs. A nominal flux of 10^5 ions / s-cm² was used, with each run concluding once a fluence of 10^7 ions/cm² was reached. The device was tested at approximately 25°C as exposed to six LET_{EFF} readpoints of 50.5 MeV-cm²/mg, 35.6 MeV-cm²/mg, 23.1 MeV-cm² / mg, 9.8 MeV-cm²/mg, 5.3 MeV-cm²/mg, and 1.0 MeV-cm²/mg. The output was monitored with an oscilloscope set to a window trigger mode that captured any events where the output shifted by ±250mV or more. The event counts are the sum of all the channels. The conditions and results for each run are summarized in the tables below. See SET Results Appendix for histograms of the transient magnitudes and transient waveforms.

Run #	DUT #	Output Condition	Temp (°C)	lon	Angle (deg)	Average Flux (ions·cm²/mg)	Fluence (# of ions)	LET _{EFF} (MeV·cm²/mg)	V _{cc} (V)	# of Events
55	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	1.65	258
56	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	3.3	366
60	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	5.5	384
127	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	1.65	209
128	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	3.3	248
129	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	5.5	276
136	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	1.65	156
137	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	3.3	206
138	1	High	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	5.5	191
231	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	1.65	122
234	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	3.3	124
235	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	5.5	157
244	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	1.65	159
245	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	3.3	152
246	1	High	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	5.5	191
276	1	High	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	1.65	33
277	1	High	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	3.3	32
278	1	High	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	5.5	17

Table 5-2. SET Run Summary for TLV4H390-SEP in Output High Condition



Table 5-3. SET Run Summary for TLV4H390-SEP in Output Low Condition										
Run #	DUT #	Output Condition	Temp (°C)	lon	Angle (deg)	Average Flux (ions·cm²/mg)	Fluence (# of ions)	LET _{EFF} (MeV·cm²/mg)	V _{cc} (V)	# of Events
61	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	1.65	243
62	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	3.3	663
63	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	50.5	5.5	ERR
131	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	1.65	180
132	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	3.3	236
133	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	35.6	5.5	266
139	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	1.65	161
140	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	3.3	200
141	1	Low	25	¹²⁹ Xe	0	1.00E+0.5	1.00E+07	23.1	5.5	267
237	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	1.65	142
238	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	3.3	162
239	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	5.5	153
243	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	9.8	5.5	182
240	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	1.65	102
241	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	3.3	155
242	1	Low	25	⁴⁰ Ar	0	1.00E+0.5	1.00E+07	5.3	5.5	174
279	1	Low	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	1.65	12
280	1	Low	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	3.3	10
281	1	Low	25	¹⁶ O	0	1.00E+0.5	1.00E+07	1	5.5	40

Figure 5-5 through Figure 5-8 show two examples of a typical transient event at 3.3V supply and LET_{EFF} = 50.5 MeV-cm² / mg. The corresponding supply current was also recorded.





6 Summary

Radiation effects of the radiation tolerant high speed comparator in space enhanced plastic TLV4H290-SEP was studied. This device passed total dose rate of up to 30krad(Si) and is SEL immune up to LET_{EFF} = 43MeV-cm²/mg and T = 125°C. SET characterization of the device was also conducted.



A SET Results Appendix

The SET histogram graphs are shown in the following section.

Figure 8-1 Run#285, Ch1, Out=High



Figure 8-2 Run#120, Ch3, Out=High



Figure 8-3 Run#120, Ch4, Out=High



Figure 8-4 Run#120, Ch1, Out=High



Figure 8-5 Run#120, Ch2, Out=High



Figure 8-6 Run#121, Ch3, Out=High



Figure 8-7 Run#121, Ch4, Out=High



Figure 8-8 Run#121, Ch1, Out=High



Figure 8-9 Run#121, Ch2, Out=High



Figure 8-10 Run#123, Ch3, Out=High



Figure 8-11 Run#123, Ch4, Out=High



Figure 8-12 Run#123, Ch1, Out=High



Figure 8-13 Run#123, Ch2, Out=High



Figure 8-14 Run#124, Ch3, Out=Low



Figure 8-15 Run#124, Ch4, Out=Low



Figure 8-16 Run#124, Ch1, Out=Low



Figure 8-17 Run#124, Ch2, Out=Low



Figure 8-18 Run#148, Ch4, Out=High



Figure 8-19 Run#148, Ch1, Out=High



Figure 8-20 Run#148, Ch2, Out=High



Figure 8-21 Run#149, Ch3, Out=High



Figure 8-22 Run#149, Ch1, Out=High



Figure 8-23 Run#149, Ch2, Out=High



Figure 8-24 Run#152, Ch3, Out=Low



Figure 8-25 Run#152, Ch4, Out=Low


Figure 8-26 Run#152, Ch1, Out=Low



Figure 8-27 Run#152, Ch2, Out=Low



Figure 8-28 Run#153, Ch3, Out=Low



Figure 8-29 Run#153, Ch4, Out=Low



Figure 8-30 Run#153, Ch1, Out=Low



Figure 8-31 Run#153, Ch2, Out=Low



Figure 8-32 Run#206, Ch3, Out=High



Figure 8-33 Run#206, Ch4, Out=High



Figure 8-34 Run#206, Ch1, Out=High



Figure 8-35 Run#206, Ch2, Out=High



Figure 8-36 Run#207, Ch3, Out=High



Figure 8-37 Run#207, Ch4, Out=High



Figure 8-38 Run#207, Ch1, Out=High



Figure 8-39 Run#207, Ch2, Out=High



Figure 8-40 Run#210, Ch3, Out=Low



Figure 8-41 Run#210, Ch4, Out=Low



Figure 8-42 Run#210, Ch1, Out=Low



Figure 8-43 Run#210, Ch2, Out=Low



Figure 8-44 Run#211, Ch3, Out=Low



Figure 8-45 Run#211, Ch4, Out=Low



Figure 8-46 Run#211, Ch1, Out=Low



Figure 8-47 Run#211, Ch2, Out=Low



Figure 8-48 Run#218, Ch3, Out=Low



Figure 8-49 Run#218, Ch4, Out=Low



Figure 8-50 Run#218, Ch1, Out=Low



Figure 8-51 Run#218, Ch2, Out=Low



Figure 8-52 Run#219, Ch3, Out=Low



Figure 8-53 Run#219, Ch4, Out=Low



Figure 8-54 Run#219, Ch1, Out=Low



Figure 8-55 Run#219, Ch2, Out=Low



Figure 8-56 Run#227, Ch3, Out=High



Figure 8-57 Run#227, Ch4, Out=High



Figure 8-58 Run#227, Ch1, Out=High



Figure 8-59 Run#227, Ch2, Out=High



Figure 8-60 Run#229, Ch3, Out=High



Figure 8-61 Run#229, Ch4, Out=High


Figure 8-62 Run#229, Ch1, Out=High



Figure 8-63 Run#229, Ch2, Out=High



Figure 8-64 Run#282, Ch3, Out=Low



Figure 8-65 Run#282, Ch1, Out=Low



Figure 8-66 Run#282, Ch2, Out=Low



Figure 8-67 Run#283, Ch3, Out=Low



Figure 8-68 Run#283, Ch1, Out=Low



Figure 8-69 Run#283, Ch2, Out=Low



Figure 8-70 Run#285, Ch3, Out=High



Figure 8-71 Run#285, Ch1, Out=High



Figure 8-72 Run#285, Ch2, Out=High



Figure 8-73 Run#286, Ch1, Out=High



Figure 8-74 Run#39, Ch2, Out=High



Figure 8-75 Run#39, Ch3, Out=High



Figure 8-76 Run#39, Ch4, Out=High



Figure 8-77 Run#39, Ch1, Out=High



Figure 8-78 Run#43, Ch2, Out=Low



Figure 8-79 Run#43, Ch3, Out=Low



Figure 8-80 Run#43, Ch4, Out=Low



Figure 8-81 Run#43, Ch1, Out=Low



Figure 8-82 Run#44, Ch2, Out=Low



Figure 8-83 Run#44, Ch3, Out=Low



Figure 8-84 Run#44, Ch4, Out=Low



Figure 8-85 Run#44, Ch1, Out=Low





8 References

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